TEM : FIB specimen preparation

Cross-sectional transmission electron microscopy of precisely selected regions from semiconductor devices
  Kirk E.C.G., D.A. Williams and H. Ahmed

Cross-sectional TEM Specimen Preparation of Semiconductor Devices by Focused Ion Beam Etching
  Park K.

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  Young R.J., E.C.G. Kirk, D.A. Williams, H. Ahmed

FIBXTEM - Focussed Ion Beam Milling for TEM Sample Preparation
  Basile D.P., R. Boylan, B. Baker, K. Hayes, D. Soza

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  Szot J., R. Hornsey, T. Ohnishi, S. Minagawa

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TEM Sample Preparation Using FIB : Practical Problems and Artifacts

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The Challenge and Methods of TEM Cross-sectioning of <0.25 micron Plugs
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Specific area planar and cross-sectional lift-out techniques : procedures and novel applications

 Specific area planar and cross-sectional lift-out techniques : procedures and novel applications
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Novel FIB-TEM preparation methods for semiconductor device characterisation and failure analysis
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Data compiled by : H. Bender, IMEC, Belgium - additions welcome at hugo.bender@imec.be
Chronologically ordered per subject
Artefacts in germanium transmission electron microscope specimens prepared by focused ion beam milling
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FIB : Focused Ion Beam

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Vieu C., J. Gierak, M. Schneider, G. Ben Assayang and J.Y. Marzin  

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**FIB : Gas assisted etching and deposition**

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Li S.X., A. Gray

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Thompson W.B., R.G. Lee

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Surface and Interface Study of Titanium Nitride on Si Substrate Produced by Dynamic Ion Beam Mixing Method
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Tracy B.

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FIB : Failure Analysis

An Application of Focused Ion Beams to Electron Beam Testing of Integrated Circuits
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Kane T., P. McGinnis, B. Engel

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Yuan C., M. Mahanpour, H-J. Lin, G. Hill

**FIB : Device modification**

Ingrated Circuit Repair Using Focused Ion Beam Milling
Harriot L.R., A. Wagner and F. Fritz

The Focused Ion Beam as an Integrated Circuit Restructuring Tool

How to Prepare Golden Devices Using Lesser Materials
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Lee R. and N. Antoniou

Performing Circuit Modification and Debugging Using Focused-Ion-Beam on Multi-Layered C4 Flip-Chip Devices
Li S.X.

Investigations of Leakage Paths in Sub-0.35 um DRAM Products Using Advanced Focused Ion Beam Techniques
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AC Hot-Carrier Effects Characterization by Circuit Modification Using Focused Ion Beam
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Hooghan K.N., K.S. Wills, P.A. Rodriguez, S. O'Connell

In-situ use of an Optical Microscope for FIB Microsurgery of Planarized Devices
Wolpert P.J. and R. Lee

Automatic determination of optimal FIB operations for improved circuit probing and fast reconfiguration
Desplats R., T. Dargnies, J-C. Courrege, P. Perdu, J-L. Noullet

Automatic determination of optimal FIB operations for improved circuit probing and fast reconfiguration
Desplats R., T. Dargnies, J-C. Courrege, P. Perdu, J-L. Noullet

**FIB : Chemical analysis**
FIB Sample Preparation to Reduce Charging for Auger Analysis
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Auger Analysis of Etch Residues in Submicrometer Via Holes using Focused Ion Beam Sample Preparation
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